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Optical Technology and Measurement for Industrial Applications 2020

**Takeshi Hatsuzawa
Rainer Tutsch
Toru Yoshizawa**
Editors

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Introduction

The first Optical Technology and Measurement for Industrial Applications Conference (OPTM) was held in Minatomirai, Yokohama JAPAN from 23 to 25 April 2019, as a part of the Optics and Photonics International Congress 2019, sponsored by the SPIE and Mechano-optics technical committee in the Japan Society of Precision Engineering. In the conference, 35 oral presentations and 15 posters were presented, which quite a lot for a first time. The topics are full of variety ranging from profilometry, data acquisition, metrology, inspection etc., showing deep interests in this technical field.

The aim of the OPTM 2020 is to provide an international opportunity for introducing up-to-date technology in the field of optical measurement and their applications for industries while at the same time, providing a networking opportunity for young researchers and students; which is another important role of the conference. Also in the venue, other optics related exhibitions and conferences will be held which is a good chance to foster interest in different technical fields. We hope your visit to the port of Yokohama will represent a new step in your technical and research career.

**Takeshi Hatsuzawa
Rainer Tutsch
Toru Yoshizawa**